An in situ transmission electron microscopy study of sintering and redispersion phenomena over size-selected metal nanoparticles: environmental effects†

Farzad Behafarid,a Sudeep Pandey,a Rosa E. Diaz,b Eric A. Stachb and Beatriz Roldan Cuenya* c

The thermal and chemical stability of micelle-synthesized size-selected Pt nanoparticles (NPs) supported on thin SiO₂ (20 nm) films was monitored in situ via transmission electron microscopy (TEM) under pure hydrogen and pure oxygen environments. The coarsening treatment was performed for 30 min at each temperature (1 Torr of either O₂ or H₂), while the TEM measurements were carried out at 1 Torr of H₂ and 0.5 Torr of O₂. Surprisingly, the NPs were found to be stable against sintering under both gaseous atmospheres up to 650 °C. Nevertheless, drastic sintering via diffusion–coalescence was observed upon annealing in H₂ at 800 °C. In contrast, an identically prepared sample demonstrated lack of agglomeration at the same temperature under O₂. The latter observation is ascribed to a strengthened chemical bond at the NP/support interface due to the formation of PtO₂ species at low temperature. Subsequently, oxidative NP redispersion – associated with some loss of Pt due to the formation of volatile PtO species – is inferred from the behavior in O₂ at/above 650 °C. In contrast, SiO₂ reduction catalyzed by the presence of the Pt NPs and Pt silicide formation was found in H₂ at 800 °C, which might play a role in the enhanced coarsening observed. Subsequent exposure of the PtSi NPs to oxygen led to the formation of Pt–SiO₂ core–shell structures. Our findings highlight the dynamic structural transformations that nanoscale materials experience under different environments and the important role played by their initial size, size distribution and dispersion on their stability against sintering.

Introduction

Metal nanoparticles (NPs) supported on oxides are currently used in gas sensing, optical and microelectronic devices, and catalysis applications.1–4 Despite the intrinsic stabilizing nature of the support, sintering is observed for small NPs under certain industrial conditions, including high temperature and exposure to various chemical environments. In the field of catalysis, the decrease in the surface-to-volume ratio associated with NP agglomeration phenomena commonly leads to deactivation,5–8 modified selectivities, and the possible formation of unwanted byproducts.6,7 Since catalysts are used in roughly 90% of all commercially produced chemicals at some stage of their manufacture, understanding their stability and transformations under different environments is of the utmost importance in order to ultimately develop more durable systems.

In this study, oxide-supported Pt NPs have been selected as a model system due to their significance in catalytic processes taking place in the petroleum industry (reforming and isomerization),8–10 environmental remediation (removal of nitrogen oxides,10 carbon monoxide and hydrocarbons from exhaust gases), and fuel cells.11–13 Since most of these important reactions are carried out at high temperature (typically between 450 °C and 800 °C),8–15 sintering is likely to occur.

Two main mechanisms have been proposed to explain NP sintering: (i) diffusion–coalescence (DC), where entire NPs move over the support surface and eventually collide and coalesce with other particles, and (ii) Ostwald-ripening (OR), where large NPs grow at the expense of smaller clusters via the detachment of the atomic or molecular species from the smaller NPs and their diffusion over the substrate surface until they meet another NP.16–17 It has been shown that in spite of previous claims by some groups, the shape of the NP size distribution is a not a reliable indication of the underlying coarsening mechanism.17,18 Some previous studies have described pronounced sintering of
Pt NPs in O₂ environments (550 °C to 700 °C), while others discussed greater sintering under H₂ at moderate temperatures (<400–500 °C). Furthermore, a significant increase in Pt/γ-Al₂O₃ dispersion was observed below 600 °C in pure oxygen, followed by NP re-agglomeration at higher temperatures. For low-on-stream hydrogen contents (4% H₂ in Ar), no sintering was detected on Pt/γ-Al₂O₃ up to 700 °C, while the sintering rate was found to drastically increase at 600 °C under low oxygen dosing (2% O₂ in Ar). Other studies reported very little coarsening of Pt NPs on γ-Al₂O₃ in a vacuum, N₂, or O₂ at temperatures up to 750 °C, while significant agglomeration occurred in wet H₂ above 500 °C. For Pt NPs on SiO₂/Si(111), no sintering was observed up to 600 °C in 0.5 Torr H₂ or O₂, while material loss via the volatilization of the PtO₂ species was observed above 450 °C under oxygen.

In order to compare sintering studies under oxidizing and reducing atmospheres from different research groups, it should be kept in mind the that coarsening phenomena are expected to be strongly dependent on environmental conditions: not only the annealing temperature and the gas environment, but also the annealing time, composition of the gas feed (content of H₂ or O₂), pressure of gaseous environment, the initial NP size and width of the NP size distribution, metal loading, initial interparticle spacing, the type of metal NP–support system, as well as material characteristics (e.g. morphology, surface area, grain size and porosity) and even artifacts from the detection method used. An example of such artifacts in the case of TEM is beam induced damage that can result in local overheating of the inspected area, as well as alteration of NP–adsorbate interaction due to beam induced dissociation of gas molecules and subsequent atomic adsorption on the NP surface.

Unfortunately, the majority of the studies available are based on ex situ microscopic investigations, and only a few cases display real-time data acquired under the given environments. Recently, direct observations of the sintering of physical-vapor-deposited (PVD) Pt NPs supported on γ-Al₂O₃ and SiO₂ thin films were made by Simonsen et al. via environmental transmission electron microscopy (E-TEM). Significant sintering was found to occur after prolonged exposure to synthetic air (21% O₂, 79% N₂) at 650 °C and a total pressure of 7.5 Torr. Similar work was done by Benavidez et al. on Pt/SiO₂, who observed no changes in the NP size distribution after 8 hours of treatment in 4.2 Torr O₂ at 550 °C, although a further increase in exposure time to ten hours led to a slight increase in the mean particle size. On the other hand, in situ extended X-ray absorption fine-structure spectroscopy (EXAFS) measurements by Matos et al. demonstrated that micelle-synthesized Pt NPs supported on nanocrystalline γ-Al₂O₃ had enhanced stability after pre-treatments in pure oxygen at ~450 °C (atmospheric pressure) when compared to similar exposures to hydrogen, where sintering was detected. Furthermore, samples pre-treated in O₂ at ~400 °C were found to be less prone to coarsening when subsequently annealed in H₂ up to 800 °C (also atmospheric pressure). In contrast, significant sintering was detected when the same sample pre-treatment was done in H₂.

In this work, we utilize E-TEM to characterize the stability of homogeneously dispersed size-selected Pt NPs synthesized via inverse micelle encapsulation and supported on SiO₂ under pure H₂ and O₂ environments (1 Torr) up to 800 °C. The role of the initial NP size, size distribution, NP/support interaction, and chemical environment in NP sintering and redispersion phenomena will be discussed.

**Results and discussion**

Fig. 1 displays E-TEM images acquired from micelle-synthesized Pt NPs on SiO₂ (sample S1 hereafter) after different in situ annealing treatments in 1 Torr hydrogen: (a) 25 °C in H₂, (b) 450 °C, (c) 650 °C, (d) 800 °C. Upon in situ annealing in hydrogen for 30 minutes, the average NP diameter was found to remain nearly stable from 25 °C (2.0 ± 0.7 nm) to 450 °C (2.2 ± 0.7 nm), while an increase in the NP size was observed at 650 °C (2.6 ± 0.9 nm). Further annealing at 800 °C led to drastic sintering (4.3 ± 1.9 nm). It should be noted that in parallel to the increase in the average NP diameter, a broadening of the NP size distribution was also observed, a clear indication of sintering.

A second sample (S2) prepared identically to S1 was annealed under similar conditions in 1 Torr of O₂: (a) at 25 °C in a vacuum, (b) after 30 min at 450 °C, (c) after 5 min at 650 °C, (d) after 30 min at 650 °C, and (e) after 30 min at 800 °C. The initial average NP diameter and size distribution was found to remain nearly constant from 25 °C (2.0 ± 0.6 nm) to 650 °C (2.3 ± 0.7 nm). Even though similar initial NP size distributions were found for both samples S1 and S2, a drastic difference in the size distribution between both samples was

![Fig. 1](image-url)
observed at 800 °C. Sample S2 annealed in O2 shows an average NP diameter of 2.5 ± 0.7 nm, in clear contrast to the 4.3 ± 1.9 nm found after annealing sample S1 in H2, highlighting the enhanced stability of the NPs against sintering in the oxidizing atmosphere. In order to further investigate this effect, sample S2 was annealed in H2 at 450 °C after the final O2 treatment, and interestingly, an increase in the NP diameter to 3.9 ± 0.8 nm was observed, Fig. 2(f).

The NP diameter distributions obtained from the analysis of the TEM images acquired in H2 (a) and O2 (b) are shown Fig. 3(a and b). Fig. 3(c) displays the evolution of the average NP diameter under the different environments with increasing annealing temperature. Additional size histograms corresponding to the images in Fig. 1 and 2 are included in the ESI.†

Our observations clearly demonstrate that Pt NPs on SiO2 are more stable against sintering up to 800 °C in an oxygen environment as compared to H2. Recent theoretical studies on Pt/γ-Al2O3 have shown that hydrogen penetrates and becomes incorporated into the metal–support interface, weakening the interaction between the NPs and the support.44,45 The heat of adsorption of H2 on platinum NPs is higher for Pt/SiO2 than for Pt/γ-Al2O3 or Pt/TiO2,46 while the metal–support interaction is larger for Pt/γ-Al2O3 as compared to Pt/SiO2.47,48 These trends indicate that a weaker NP/support interaction exists for Pt/SiO2 as compared to Pt/γ-Al2O3 in hydrogen.

Fig. 4 shows two sets of consecutive images of the Pt NPs at 650 °C under H2 (a–c) and O2 (d–f) environments with their respective time lapse on each image. Our in situ TEM observations directly demonstrate the mobility of the NPs in both environments. In addition, as can be seen in Fig. 5(b), the presence of several NPs with similar size to those in the as-prepared sample surrounding a significantly larger (coarsened) Pt NP also suggests that the diffusion–coalescence process is responsible for the sintering observed under hydrogen at 800 °C.

Nanoparticle–support interactions have been reported to increase in O2 environments for Pt NP/oxide support systems, leading to a decrease in NP mobility across the substrate surface.24,25,32,33 Therefore, diffusion–coalescence processes are less likely in oxygen environments,25 as was observed here, even up to 800 °C. However, although a stronger metal–support interaction would reduce the NP mobility and hinder the diffusion coalescence process, it would also reduce the energy barrier for metal-atom detachment from the NPs.16,17 Parker et al.16 had derived the total energy barrier involved in the Ostwald ripening process to be $E_{\text{tot}} = \Delta H_{\text{sub}} - E_{\text{ad}}^* + H_m^*$ in which $E_{\text{tot}}$ is equal to the metal’s bulk sublimation enthalpy ($\Delta H_{\text{sub}}$), minus the adsorption energy of a monomer on the support ($E_{\text{ad}}^*$), plus the diffusion barrier of a metal monomer atom on the support ($H_m^*$). This equation clearly shows that a higher $E_{\text{ad}}^*$
lowers the overall OR energy barrier. In other words, a higher metal–support binding energy would make it more energetically favorable for an atom to break its bonds from the parent NP and make new bonds with the support. Such atom-by-atom detachment could be the initial step for both NP redispersion or NP growth via OR.49 In general, NP redispersion occurs when the detached atoms bond to trap sites on the support as either individual atoms or small clusters, while in the OR processes the detached atoms reach other NPs and contribute to their growth.49 Variations in experimental conditions may change the most favorable trend, which might explain some of the apparent discrepancies in the literature regarding the coarsening behavior of metallic NPs in oxidizing environments. For instance, several previous studies have found that supported Pt NPs sinter significantly in O$_2$ at temperatures $\geq 600$ °C,20,23,28,29,50 and oxide species,$^4,37,51$ were suggested to act as intermediates in Ostwald ripening processes. On the other hand, we have recently shown via in situ X-ray absorption fine-structure spectroscopy (EXAFS) and ex situ TEM that Pt NPs on $\gamma$-Al$_2$O$_3$ are more stable against sintering at 450 °C under pure O$_2$ as compared to H$_2$.35 The latter is in agreement with our current study as well as other reports$^{21,34}$ showing NP growth under H$_2$ and NP redispersion under O$_2$ environments.

In addition, by comparing our present results with the related literature, it is apparent that having initially narrow NP size and interparticle distance distributions is also important. NPs synthesized using the inverse micelle encapsulation method have been shown to have a better size selection as compared to those prepared by other conventional synthesis methods such as physical vapor deposition (PVD).17,22,33 NP size homogeneity, results in all particles having similar surface energies.49 Since the difference in the NP's surface energy is the driving force for Ostwald ripening processes, OR phenomena will be suppressed for samples with narrow NP size distributions.17 In addition, if the interparticle distance is large, the probability of migrating species or entire NPs colliding with other particles will decrease, hence decreasing the sintering rate and favoring redispersion.43 In fact, in previous experiments in which sintering in O$_2$ was observed,19,22 the average interparticle distances were much smaller than the ones considered here (3–5 nm vs. 18–20 nm), and the initial size distributions were also broader. Additionally, in related experiments where sintering was observed under oxidizing environments,19,22 longer annealing times were employed (6 h versus 30 min in our case at 650 °C).

Interestingly, in our in situ study a change in the contrast of the NPs (dimmer) was observed under O$_2$ above 650 °C in the TEM images of Fig. 2(d and e), suggesting that the dimmer NPs are flatter and likely highly oxidized. This conclusion stems from the mass-thickness contrast mechanism prevalent in these bright-field electron micrographs; namely, for the same diameter, a lighter particle has either lighter atoms (e.g. contains more oxygen) or is thinner (e.g. flatter). A previous high pressure X-ray photoelectron spectroscopy (XPS) study from our group revealed that reduced Pt NPs that are exposed to 0.5 Torr of oxygen at temperatures up to 600 °C are completely oxidized and form PtO.18 Oxidized Pt NPs have been shown to flatten as compared to metallic NPs.$^{52,53}$ Therefore, the lack of coarsening in this study under an O$_2$ environment could be understood in terms of an enhanced metal–support interaction, hindering the diffusion of NPs and favoring NP redispersion. Another possibility that may play a role in the lack of sintering observed in oxygen is the elimination of a fraction of the volatile PtO$_2$.
species that are desorbed from the NPs by the microscope pumping system before re-deposition.\textsuperscript{16} Surprisingly, an increase in the mean particle size was observed for the sample that was previously annealed in O\textsubscript{2} at 800 °C upon subsequent exposure to 1 Torr of H\textsubscript{2} at 450 °C. Although this sample had an average NP size similar to that of the as prepared sample, the coarsening observed upon low-temperature H\textsubscript{2} exposure opposes the lack of coarsening displayed by the as-prepared sample after a similar treatment. This observation may be understood in terms of NP redispersion during the treatment in oxygen resulting in small and flat clusters or isolated ions (likely oxidized) in between the NPs, which have a very weak contrast and therefore are hardly visible in the TEM images. Upon subsequent annealing in a reducing environment, such small islands would be quickly reduced and become mobile, resulting in the NP growth observed here.

High-resolution images of NPs in H\textsubscript{2} at 800 °C (a–c) and after cooling down to 25 °C and exposure to O\textsubscript{2} (d) are shown in Fig. 5. The crystalline structure of these NPs was determined based on their shape and the d-spacing measured from the observed lattice fringes. Remarkably, the lattice fringes observed in (a, b) are not consistent with metallic fcc Pt. The large NP shown in Fig. 5(a) has a square shape consistent with a faceted NP, seen from the [100] direction. However, the lattice spacing is almost twice that expected for d\textsubscript{200} in metallic Pt (d\textsubscript{100} is forbidden in the fcc structure). Similarly, the NP shown in Fig. 5(b) has a mirror symmetry consistent with a NP seen in [110] direction, and again the lattice distance is twice that of d\textsubscript{220} in metallic Pt. This observation suggests that the restriction on forbidden \{h, k, l\} planes in an fcc lattice has been lifted. In addition, the fringes in a square metallic Pt NP are expected to run in a diagonal direction (45° rotated as compared to the edges of the NP)\textsuperscript{45} while here the fringes run parallel to the NP edges, Fig. 5(a). These observations are consistent with the formation of Pt silicide with a cubic Pt\textsubscript{3}Si structure (L\textsubscript{1\textsubscript{2}} with a lattice parameter of 3.9 Å).\textsuperscript{34,45,54,55} For Pt–SiO\textsubscript{2} systems, such silicide formation has been reported to occur under hydrogen environment at/above 600 °C\textsuperscript{44,54,55} but not in a vacuum, even after treatments up to 800 °C.\textsuperscript{56} This phenomenon reflects the catalytic reduction of SiO\textsubscript{2} in H\textsubscript{2}, mediated by the presence of the Pt NPs.\textsuperscript{47,57–59} The reduction of the ultrathin SiO\textsubscript{2} membrane (20 nm) under our experimental conditions is also evident in Fig. 5(c), in which the round feature has a d-spacing of 3.1 Å, which is consistent with silicon (111).\textsuperscript{57,58} Such reduction of the SiO\textsubscript{2} support in our sample most likely occurred under a Pt NP, which has subsequently disappeared due to coarsening, exposing the NP/support interface. Interestingly, a different type of fringe could be seen in the lower and upper edges of the square NP in Fig. 5(a). Since the NP thickness decreases at the side facets, this may allow the Si substrate features to become dominant. These lattice fringes (d-spacing of 3.1 Å) match those of Si(111), confirming that the substrate is reduced underneath the NP.

Fig. 5(d) shows the sample that was annealed in H\textsubscript{2} at 800 °C after it was cooled to 25 °C and was exposed to O\textsubscript{2}. The NPs

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Fig. 6: Schematic cartoon depicting environmental effects on NP morphology and mobility. (a) Oxidized as prepared sample. (b) Reduction of the NPs under H\textsubscript{2} at 450–650 °C and moderate NP mobility. (c) Annealing at high temperature (800 °C) under H\textsubscript{2} results in catalytic reduction of SiO\textsubscript{2}, Pt–Si alloy formation, and severe coarsening. (d) Exposure of the sample coarsened in H\textsubscript{2} to O\textsubscript{2} results in the formation of core–shell structures. (e) In contrast, heat treatment in O\textsubscript{2} (450–650 °C) only results in moderate mobility. (f) High temperature annealing in O\textsubscript{2} results in NP disruption and redispersion as well as NP flattening. (g) At last, annealing the sample previously treated in O\textsubscript{2}, under a H\textsubscript{2} environment results in coarsening due to the reduction and agglomeration of small Pt oxide clusters dispersed between the original NPs.
show a core–shell structure with a crystalline core and an amorphous shell. The 2.0 Å lattice spacing of the core matches the metallic structure of Pt \((d_{320})\). These data evidence that \(O_2\) exposure results in the outward segregation of Si from Pt silicide due its higher oxygen affinity and the formation of a SiO\(_x\) shell, leaving the NP core as pure Pt.\(^{59}\) However, the possible presence of Pt oxide species in the NP shell cannot be completely ruled out. The inset in Fig. 5(d) shows additional examples of the observed core–shell structures.

Fig. 6 schematically summarizes our observations for both samples. The as-prepared samples are initially oxidized and have a narrow size distribution \((a)\). Annealing in a hydrogen environment in the temperature range of 450–650 °C results in the reduction of the NPs to metallic Pt followed by faceting, with only moderate mobility and limited coarsening \((b)\). Increasing the temperature to 800 °C in \(H_2\) results in catalytic SiO\(_2\) reduction due to the presence of the Pt NPs, Pt silicide formation, and severe NP sintering, \((c)\). Lastly, cooling the sample to room temperature and exposing it to \(O_2\) results in the formation of core–shell structures, \((d)\).

In clear contrast, annealing the analogous as-prepared sample in \(O_2\) at 450–650 °C has no significant effect on the NP average size, Fig. 2(e). Although moderate mobility is expected, the large interparticle distance in our sample hinders the diffusion–coalescence in the time scale of this study. However, annealing at high temperature led to the disruption of the NPs and their redispersion, resulting in the formation of small Pt oxide clusters in between the larger NPs, Fig. 2(f). A final annealing of the sample at 450 °C in \(H_2\) after cooling the sample to room temperature resulted in the reduction of the PtO\(_x\) clusters and their consequent agglomeration with Pt NPs, which is observed as an overall coarsening effect.

**Conclusion**

Our *in situ* TEM study of the stability of micelle-synthesized Pt NPs revealed drastic changes in the NP morphology with increasing temperature in hydrogen, with marked sintering via diffusion–coalescence starting at 650 °C and being most prominent at 800 °C, where the formation of large faceted NPs was observed. The reduction of the SiO\(_2\) support and the formation of Pt silicide were demonstrated based on HRTEM images. Exposing the platinum silicide to \(O_2\) at room temperature resulted in the outward diffusion of Si and formation of a silicon oxide shell and a metallic Pt core. In contrast, no sintering was observed when an identical sample was annealed in pure oxygen under the same conditions, *i.e.* up to 800 °C.

To the best of our knowledge, this is the only experimental study that shows enhanced stability of small Pt NPs against coarsening up to 800 °C in \(O_2\). Some groups have reported significant coarsening under \(O_2\) (550 °C to 700 °C).\(^{18-29,39}\) Others have shown minimal sintering in \(O_2\),\(^{30-36}\) but at much lower temperatures (<550 °C). The enhanced NP stability in this study is assigned to the strengthening of the Pt NP/SiO\(_2\) interface upon PtO\(_x\) formation and to NP redispersion. This is in agreement with the observed change in the NP contrast (dimmer NPs indicative of flatter NPs). The NP redispersion was also confirmed by the subsequent low temperature (450 °C) coarsening observed for this sample in \(H_2\) due to the reduction of small ions/PtO\(_x\) clusters distributed between the larger NPs and their contribution to NP growth. Although silicon oxide has been traditionally considered as a “non-reducible” support, here we provide direct experimental evidence for the role of Pt NPs in the catalytic reduction of SiO\(_2\) to Si under much lower temperatures than those required in the absence of the NPs. Also, it was found that the Pt NP–SiO\(_2\) system could form a core–shell structure due to Pt silicide formation (core) upon annealing in \(H_2\) and the subsequent formation of a SiO\(_2\) shell upon exposure to \(O_2\). Cyclic treatments in reducing and oxidizing environments are a common practice in the catalysis industry, and for the case of Pt NP–SiO\(_2\), such treatments could result in the encapsulation of the Pt NPs by a SiO\(_2\) layer.

**Experimental**

The technique of inverse micelle encapsulation\(^{4,60}\) was employed to prepare the samples presented here. A polystyrene-2vinylpyridine [PS(16 000)–P2VP(3500)] diblock copolymer was dissolved in toluene to create inverse micelles, and the micellar cages were loaded with a H\(_2\)PtCl\(_6\) platinum precursor with a metal-to-P2VP ratio of 0.1. The samples were then drop coated onto SiO\(_2\)(20 nm)/Si TEM grids (SO100-A20Q33). Two samples were prepared using the same NP solution. Subsequently, the samples underwent an \(O_2\) plasma treatment in ultrahigh vacuum (UHV) for the removal of the polymeric ligands \((P_{O_2} = 4 \times 10^{-5} \text{ mbar}, 120 \text{ min})\). XPS measurements confirmed the absence of chlorine and carbon contamination after the plasma treatment. The as-prepared Pt NPs were found to be oxidized due to the \(O_2\)-plasma treatment.\(^4\) Since the samples were transferred in air to Brookhaven National Laboratory (BNL) for the E-TEM work, a 5 min \(O_2\)-plasma treatment was done at BNL before the microscopy measurements in order to ensure the complete removal of adventitious carbon from the NP surface.

*In situ* TEM analysis was done using an aberration-corrected 300 keV transmission electron microscope (FEI Titan 80-300) equipped with a differentially pumped environmental cell and a post-specimen CEOS aberration-corrector. Image acquisition used both a Gatan Orius camera and a Gatan Ultrascan camera. Two identically-prepared but separate samples were used for the \(H_2\) and \(O_2\) treatments. In our experiments, the pressure was maintained at 1 Torr at all temperatures during the treatments in hydrogen (sample S1) and oxygen (sample S2), but reduced to 0.5 Torr for the acquisition of the images in oxygen. In both environments, the investigated sample temperatures were: 25 °C (room temperature), 450 °C, 650 °C, and 800 °C. The samples were kept for 30 min at each temperature. The sample temperature was measured with a thermocouple attached to a furnace in the vicinity of the sample and may have a ±10 °C error as compared to the actual temperature on the TEM grid. For the 650 °C treatment in \(O_2\), two datasets were acquired, a first one after a 5 minute
exposure, and a second one after 30 minutes. After the treatment of S2 in oxygen at 800 °C, the sample was subsequently reduced in H2 at 450 °C while sample S1 treated at 800 °C in H2, was cooled to room temperature (25 °C), and was exposed to O2.

Beam-damage effects were carefully monitored. The beam density varies between different images depending on the magnification, with higher density for higher magnification. A typical dose of 800 electrons Å−2 for a magnification of 530k× and a value of 400 electrons Å−2 for a magnification of 130k× were used. The exposure time was varied on the order of 0.1–1 seconds. Drastic changes were observed in our sample morphology under combined O2 and e-beam irradiation, in particular, the formation of shell-like crystalline structures around the NPs suggestive of significant oxidation due to e-beam-induced O2 dissociation. Such structures were found to grow into whiskers upon increasing e-beam exposure time (not shown). Such effects were not observed under identical dosing conditions in hydrogen. Therefore, in order to minimize undesired measurement artifacts, which might obscure the real O2-mediated sintering phenomena, i.e., those occurring in the absence of the electron beam, images in O2 were acquired immediately after reaching a given temperature. The beam was then turned off, and then the sample was kept at the given temperature for 30 min, when the beam was turned back on to check the final state of the sample.

Acknowledgements

Financial support from the U.S. Department of Energy (DE-FG02-08ER15995) is greatly appreciated. Use of the electron microscopy facilities at the Center for Functional Nanomaterials, Brookhaven National Laboratory, which is supported by the U.S. Department of Energy, Office of Basic Energy Sciences, under contract DE-AC02-98CH10886 is acknowledged. This work was also partially funded by the Cluster of Excellence Ruhr Explores Solvation (RESOLV) (EXC 1069) funded by the Deutsche Forschungsgemeinschaft.

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